

## REMARKS / ARGUMENTS

In complete response to the Office Action dated January 5, 2009, on the above identified application, reconsideration is respectfully requested. Claims 18-35 are pending in this application.

### Claim Rejections Under 35 U.S.C. § 103:

Claims 18, 19, 21, 24-28, and 32-35 are rejected under 35 U.S.C. 103(a) as being unpatentable over Sato et al. (US 2001/0048973). The applicants respectfully contend that these claims are not unpatentable over Sato '973.

On page 3 of the instant official action, the Examiner states "Sato does not specifically teach feeding a hydrazine gas and a silylhydrazine or trisilylamine as the silicon containing precursor gas. However, Sato does teach that any silicon compound may be used that is suitable for CVD [0031] and that silylhydrazines may be formed in a preliminary reaction chamber and then fed to the reaction chamber [0062]."

The applicants agree with the Examiner that Sato '973, does not specifically teach the feeding of hydrazine gas and a silylhydrazine or trisilylamine as the silicon containing precursor gas. The Applicants respectfully contend that while [0031] of Sato '973 states that "any silicon compound" may be used, such language is overly broad/inclusive and therefore does not support the 103(a) rejection.

There are a nearly infinite number of silicon containing compounds (some of which presumably have yet to be discovered) which could be suitable for a CVD type deposition. The fact that Sato '973 states 'any silicon compound' is suitable is akin to stating any element on the periodic table would be suitable. Both statements are overly broad, and the Applicants respectfully contend that one of skill in the art would not understand the language of Sato '973 to teach or suggest feeding a hydrazine gas and a silylhydrazine or trisilylamine as the silicon containing precursor gas."

For at least these reasons, the Applicants respectfully contend that the basis for this rejection deserves reconsideration.

Claims 18, 21, 24, 25, 26, and 35 are rejected under 35 U.S.C. 103(a) as being unpatentable over Sato et al. (US 2001/0048973) as applied above in view of Ishikawa (JP 06338497).

The Applicants respectfully contend that the addition of Ishikawa '497 does not remedy the aforementioned deficiencies of the Sato '973 reference. Further, the Applicants respectfully contend that the proposed combination of Sato '973 and Ishikawa '497, teach away from the instant invention, as Ishikawa '497 discloses a combination of trisilylamine and ammonia. One of skill in the art would not recognize the ammonia (one nitrogen atom) of Ishikawa '497 to teach or suggest a process utilizing hydrazines (two nitrogen atoms), as taught by the instant invention.

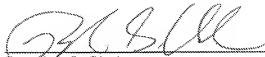
For at least these reasons, the Applicants respectfully contend that the basis for this rejection deserves reconsideration.

Claims 20, 22, 23, and 29-31 are rejected under 35 U.S.C. 103(a) as being unpatentable over Sato et al. (US 2001/0048973) as applied above in view of Fessenden et al. The Applicants respectfully contend that the addition of Fessenden does not overcome the aforementioned deficiencies of Sato '973. For at least this reason, the Applicants respectfully contend that the basis for this rejection deserves reconsideration.

## CONCLUSION

Accordingly, it is believed that the present application now stands in condition for allowance. Early notice to this effect is earnestly solicited. Should the Examiner believe a telephone call would expedite the prosecution of the application, he is invited to call the undersigned attorney at the number listed below.

Respectfully submitted,



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